October 30th to November 3rd, 2018

11th LEEM/PEEM CHONGQING

The 11th LEEM/PEEM workshop

LEEM/PEEM is a biennial meeting reviewing the status of LEEM, PEEM, SPEEM, SPELEEM, XPEEM and related techniques. The meeting promotes and disseminates applications of surface microscopy with low energy electrons to a broad audience of interested scientists.

The workshop highlights the most recent scientific advances as well as instrumental developments. Topics will cover surfaces, thin films, organic films, surface chemistry, magnetism, time resolved methods, instrumental advances and novel applications of LEEM and PEEM to other subject areas.

A Welcome Reception will be held from 6:00 pm on Tuesday, 30 Oct. 2018 located in the Radisson Blu Hotel, Chongqing. (www.radissonblu.com/chongqing-shapingba)

The main scientific program on October 30 - November 3 will feature contributed talks and presentations by six Distinguished Guest Lecturers in a single session format, as well as a poster session. This will be preceded by a special LEEM/PEEM Tutorial session, which will provide a unique experience for students and scientists new to the field to learn from Tutorial Instructors who are leading experts in the field. While open to all, participation in the tutorials requires additional registration and space is limited.

Important Dates

1. March 25, 2018 Call for abstracts
2. April 25, 2018 Registration opens
3. June 15, 2018 Deadline for abstract submission
4. August 15, 2018 Notification of acceptance
5. September 30, 2018 Early registration deadline
6. September 25, 2018 Cutoff date for rooms at the Radisson Blu Hotel

International advisory committee:
Michael Altman (Hong Kong, China) Ernst Bauer (USA)
Gary Kellogg (USA) Takanori Koshikawa (Japan)
Andrea Locatelli (Italy) Bene Poelsema (Netherlands)
Ruud Tromp (USA) Andreas Schmid (USA)

Local organizing committee:
Wen-Xin Tang (CQU), Fu Qiang (Dalian Institute of Chemical Physics, CAS),
Michael Altman (HKUST), Haifei Shi (Chongqing Institute of Green and Intelligent Technology, CAS), Zheng Wei (CQU), Meng Li (CQU).

Program committee:
Wen-Xin Tang (CQU), Fu Qiang (Dalian Institute of Chemical Physics, CAS),
Michael Altman (HKUST), Zefang Ren (Dalian Institute of Chemical Physics, CAS),
Weishi Yan (ShanghaiTech University), Zhicheng Wu (Tsuda University),
Haifeng Ding (Nanjing University), Guowei Lu (Peking University),
Jingguan Lin (Changchun University of Science and Technology),
Shouguo Wang (University Science and Technology Beijing)